

*Claim Amendments, 22 August 2001*

3. (amended) The method of claim 1 wherein said electrolyte layer comprises a material selected from a group consisting of [comprising:] yttria stabilized zirconia, a mixed ion and electron conductor, and a composite of a metal and an ion conductor.
6. (amended) The method of claim 1 wherein said interconnect layer comprises a material selected from a group consisting of [comprising:] metal, alloy, and ceramic.
9. (amended) The method of claim 8 wherein said thin-film deposition technique comprises a technique selected from a group consisting of [comprising:] aqueous spray deposition, tape casting, co-casting onto said anode layer, thermal spray, plasma spray, and directed vapor deposition.
13. (amended) The method of claim 12 wherein said thin-film deposition technique comprises a technique selected from a group consisting of [comprising:] thermal spray, directed vapor deposition, plasma spray, tape-casting, and co-casting onto a porous catalyst layer.
17. (amended) The method of claim 16 wherein said ceramic-to-metal joining technique comprises a technique selected from a group consisting of [comprising:] transient liquid phase bonding and brazing.
21. (twice amended) The method of claim 20 wherein said porous catalyst layers comprise a material selected from a group consisting of [comprising:] a mixed ion and electron conducting ceramic and a composite of metal and an ion conducting ceramic.
23. (amended) The method of claim 22 wherein said thin-film deposition technique comprises a technique selected from a group consisting of [comprising:] tape-casting, screen printing, thermal spray, and plasma spray.
41. (amended) The method of claim 40 wherein said connecting comprises a technique selected from a group consisting of [comprising:] ceramic-ceramic bonding, transient liquid phase bonding, and brazing.